

## EAST Search History

## EAST Search History (Prior Art)

| Ref # | Hits   | Search Query  | DBs   | Default Operator | Plurals | Time Stamp          |
|-------|--------|---|---|------------------|---------|---------------------|
| L1    | 278    | (dehumidif\$) near10<br>(gas) near10 (oxygen<br>or "O2" or "O.sub.2")         | US-PGPUB;<br>USPAT; USOCR;<br>FPRS; EPO;<br>JPO;<br>DERWENT;<br>IBM_TDB | OR               | ON      | 2009/12/27<br>15:38 |
| L2    | 0      | I1 and (lithograph\$ or<br>photolithograph\$)                                 | US-PGPUB;<br>USPAT; USOCR;<br>FPRS; EPO;<br>JPO;<br>DERWENT;<br>IBM_TDB | OR               | ON      | 2009/12/27<br>15:39 |
| L3    | 129495 | (water or "H2O" or "H.<br>sub.2O") near5<br>(oxygen or "O2" or "O.<br>sub.2") | US-PGPUB;<br>USPAT; USOCR;<br>FPRS; EPO;<br>JPO;<br>DERWENT;<br>IBM_TDB | OR               | ON      | 2009/12/27<br>15:39 |
| L4    | 50     | I1 same I3  | US-PGPUB;<br>USPAT; USOCR;<br>FPRS; EPO;<br>JPO;<br>DERWENT;<br>IBM_TDB | OR               | ON      | 2009/12/27<br>15:39 |
| L5    | 0      | ("134"/\$).ccls. and I4   | US-PGPUB;<br>USPAT; USOCR;<br>FPRS; EPO;<br>JPO;<br>DERWENT;<br>IBM_TDB | OR               | ON      | 2009/12/27<br>15:40 |
| S1    | 8      | ("6249932" or<br>"6974505" or<br>"6922867" or<br>"6391090").pn.               | US-PGPUB;<br>USPAT; USOCR;<br>FPRS; EPO;<br>JPO;<br>DERWENT;<br>IBM_TDB | OR               | ON      | 2009/12/26<br>11:24 |
| S2    | 4      | ("6249932" or<br>"6974505" or<br>"6922867" or<br>"6391090").pn.               | USPAT   | OR               | ON      | 2009/12/26<br>11:25 |
| S3    | 0      | "20040074521".pn.   | USPAT   | OR               | ON      | 2009/12/26<br>11:27 |
| S4    | 1      | "20040074521".pn.   | US-PGPUB;<br>USPAT  | OR               | ON      | 2009/12/26<br>11:28 |

|     |      |  |  |    |    |                     |
|-----|------|--|--|----|----|---------------------|
| S5  | 4377 | (room adj temperature) near5 (ambient adj temperature)   | US-PGPUB; USPAT  | OR | ON | 2009/12/26<br>16:21 |
| S6  | 4788 | (room adj temperature) near5 (ambient adj temperature)   | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2009/12/26<br>16:22 |
| S7  | 0    | (room adj temperature) near3 (ambient adj temperature)with (lithography)   | US-PGPUB; USPAT  | OR | ON | 2009/12/26<br>16:23 |
| S8  | 1    | (room adj temperature) near3 (ambient adj temperature) same (lithography)  | US-PGPUB; USPAT  | OR | ON | 2009/12/26<br>16:24 |
| S9  | 2    | (room adj temperature) near3 (ambient adj temperature) same (lithograph\$ or photolithograph\$)  | US-PGPUB; USPAT  | OR | ON | 2009/12/26<br>16:24 |
| S10 | 0    | (oxidation or oxidizing or oxidized or oxidize) near10 (carbon) near5 (deposit or residue or film or contaminant or impurity or particle or particulate) with ((room or ambient) adj4 temperature) same (lithograph\$ or photolithograph\$)                  | US-PGPUB; USPAT  | OR | ON | 2009/12/26<br>17:11 |
| S11 | 0    | (oxidation or oxidizing or oxidized or oxidize) near10 (carbon) near5 (deposit or residue or film or contaminant or impurity or particle or particulate or contamination) with ((room or ambient) adj4 temperature) same (lithograph\$ or photolithograph\$) | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2009/12/26<br>17:12 |

|     |     |  |   |    |    |                     |
|-----|-----|--|---|----|----|---------------------|
| S12 | 0   | (oxidation or oxidizing or oxidized or oxidize) near10 (carbon) with ((room or ambient) adj4 temperature) same (lithograph\$ or photolithograph\$)                             | US-PGPUB;<br>USPAT; USOCR;<br>FPRS; EPO;<br>JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2009/12/26<br>17:12 |
| S13 | 7   | (oxidation or oxidizing or oxidized or oxidize) near10 (carbon) with ( temperature) same (lithograph\$ or photolithograph\$)   | US-PGPUB;<br>USPAT; USOCR;<br>FPRS; EPO;<br>JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2009/12/26<br>17:12 |
| S14 | 233 | (oxidation or oxidizing or oxidized or oxidize) near10 (carbon) with ( temperature) and (lithograph\$ or photolithograph\$)  | US-PGPUB;<br>USPAT; USOCR;<br>FPRS; EPO;<br>JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2009/12/26<br>17:13 |
| S15 | 195 | S14 and (wafer or semiconductor or silicon)  | US-PGPUB;<br>USPAT; USOCR;<br>FPRS; EPO;<br>JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2009/12/26<br>17:14 |
| S16 | 18  | (oxidation or oxidizing or oxidized or oxidize) near10 (carbon) with ( (room or ambient) near5 temperature) and (lithograph\$ or photolithograph\$)                            | US-PGPUB;<br>USPAT; USOCR;<br>FPRS; EPO;<br>JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2009/12/26<br>17:16 |
| S17 | 19  | (oxidation or oxidizing or oxidized or oxidize or oxidant) near10 (carbon\$6) with ( (room or ambient) near5 temperature) and (lithograph\$ or photolithograph\$)              | US-PGPUB;<br>USPAT; USOCR;<br>FPRS; EPO;<br>JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2009/12/26<br>17:21 |
| S18 | 19  | (oxidation or oxidizing or oxidized or oxidize or oxidant) near10 (carbon or carbonaceous) with ( (room or ambient) near5 temperature) and (lithograph\$ or photolithograph\$) | US-PGPUB;<br>USPAT; USOCR;<br>FPRS; EPO;<br>JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2009/12/26<br>17:21 |

|     |       |   |   |    |    |                     |
|-----|-------|---|---|----|----|---------------------|
| S19 | 8     | (oxidation or oxidizing or oxidized or oxidize or oxidant) near10 (carbon or carbonaceous or carbon adj gas or carbon adj monoxide or carbon adj dioxide or "CO" or "CO.sub.2" or "CO2") with (temperature or centigrade or celcius) same (lithograph\$ or photolithograph\$) | US-PGPUB;<br>USPAT; USOCR;<br>FPRS; EPO;<br>JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2009/12/26<br>17:33 |
| S20 | 18994 | (oxidation or oxidizing or oxidized or oxidize or oxidant) near10 (carbon or carbonaceous or carbon adj gas or carbon adj monoxide or carbon adj dioxide or "CO" or "CO.sub.2" or "CO2") with (temperature or centigrade or celcius)  | US-PGPUB;<br>USPAT; USOCR;<br>FPRS; EPO;<br>JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2009/12/26<br>17:35 |
| S21 | 9547  | (oxidation or oxidizing or oxidized or oxidize or oxidant) near10 ( carbon adj gas or carbon adj monoxide or carbon adj dioxide or "CO" or "CO.sub.2" or "CO2") with (temperature or centigrade or celcius)   | US-PGPUB;<br>USPAT; USOCR;<br>FPRS; EPO;<br>JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2009/12/26<br>17:35 |
| S22 | 147   | S21 and (lithograph\$ or photolithograph\$)   | US-PGPUB;<br>USPAT; USOCR;<br>FPRS; EPO;<br>JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2009/12/26<br>17:35 |
| S23 | 129   | S22 and (wafer or semiconductor or silicon or mask)   | US-PGPUB;<br>USPAT; USOCR;<br>FPRS; EPO;<br>JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2009/12/26<br>17:36 |

|     |      |  |   |    |    |                     |
|-----|------|--|---|----|----|---------------------|
| S24 | 7239 | (oxidation or oxidizing or oxidized or oxidize or oxidant) near5 ( carbon adj gas or carbon adj monoxide or carbon adj dioxide or "CO" or "CO.sub.2" or "CO2") with (temperature or centigrade or celcius) | US-PGPUB;<br>USPAT; USOCR;<br>FPRS; EPO;<br>JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2009/12/26<br>17:38 |
| S25 | 106  | S24 and (lithograph\$ or photolithograph\$)  | US-PGPUB;<br>USPAT; USOCR;<br>FPRS; EPO;<br>JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2009/12/26<br>17:39 |
| S26 | 652  | ("CO" ) near5 (oxidize or oxidation or oxidizing or oxidized) with (low) near4 (temperature)   | US-PGPUB;<br>USPAT; USOCR;<br>FPRS; EPO;<br>JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2009/12/26<br>17:42 |
| S27 | 26   | S26 and (lithograph\$ or photolithograph\$)  | US-PGPUB;<br>USPAT; USOCR;<br>FPRS; EPO;<br>JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2009/12/26<br>17:42 |
| S28 | 740  | (carbon adj dioxide or carbon adj monoxide or "CO.sub.2" or "CO2" ) near5 (oxidize or oxidation or oxidizing or oxidized) with (low) near4 (temperature)   | US-PGPUB;<br>USPAT; USOCR;<br>FPRS; EPO;<br>JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2009/12/26<br>17:44 |
| S29 | 26   | S27 and (lithograph\$ or photolithograph\$)  | US-PGPUB;<br>USPAT; USOCR;<br>FPRS; EPO;<br>JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2009/12/26<br>17:44 |
| S30 | 285  | (carbon adj dioxide or carbon adj monoxide or "CO.sub.2" or "CO2" ) near5 (oxidize or oxidation or oxidizing or oxidized) with ((ambient or room) near4 (temperature) or "25 adj C")                       | US-PGPUB;<br>USPAT; USOCR;<br>FPRS; EPO;<br>JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2009/12/26<br>17:51 |

|     |     |   |   |    |    |                     |
|-----|-----|---|---|----|----|---------------------|
| S31 | 174 | (carbon adj dioxide or carbon adj monoxide or "CO.sub.2" or "CO2" ) near5 (oxidize or oxidation or oxidizing or oxidized) near4 ((ambient or room) near4 (temperature) or "25 adj C")   | US-PGPUB;<br>USPAT; USOCR;<br>FPRS; EPO;<br>JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2009/12/26<br>17:51 |
| S32 | 225 | (carbon adj dioxide or carbon adj monoxide or "CO.sub.2" or "CO2" ) near5 (oxidize or oxidation or oxidizing or oxidized) near10 ((ambient or room) near4 (temperature) or "25 adj C")  | US-PGPUB;<br>USPAT; USOCR;<br>FPRS; EPO;<br>JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2009/12/26<br>17:52 |
| S33 | 3   | S32 and (lithograph\$ or photolithograph\$)   | US-PGPUB;<br>USPAT; USOCR;<br>FPRS; EPO;<br>JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2009/12/26<br>17:52 |
| S34 | 16  | (carbon adj4 (deposit or residue or film or particle or amorph\$4)) near10 (oxidation or oxidizing or oxidized or oxidize) with ((room or ambient or low) near5 temperature) and (lithograph\$ or photolithograph\$)  | US-PGPUB;<br>USPAT; USOCR;<br>FPRS; EPO;<br>JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2009/12/26<br>17:59 |
| S35 | 30  | ((carbon or carbonaceous) near10 (deposit or residue or film or particle or amorph\$4 or contaminant or contamination or impurity)) near10 (oxidation or oxidizing or oxidized or oxidize) with ((room or ambient or low) near5 temperature or "25" adj3 (celcius or centigrade or degree)) and (lithograph\$ or photolithograph\$) | US-PGPUB;<br>USPAT; USOCR;<br>FPRS; EPO;<br>JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2009/12/26<br>18:04 |

|     |   |  |   |    |    |                     |
|-----|---|--|---|----|----|---------------------|
| S36 | 1 | (hydrocarbon) near10<br>(oxidation or oxidizing<br>or oxidized or oxidize)<br>with ((room or<br>ambient) near5<br>temperature or "25"<br>adj3 (celcius or<br>centigrade or degree))<br>and (lithograph\$ or<br>photolithograph\$)  | US-PGPUB;<br>USPAT; USOCR;<br>FPRS; EPO;<br>JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2009/12/26<br>18:10 |
| S37 | 1 | (hydrocarbon) with<br>(oxidation or oxidizing<br>or oxidized or oxidize)<br>with ((room or<br>ambient) near5<br>temperature or "25"<br>adj3 (celcius or<br>centigrade or degree))<br>and (lithograph\$ or<br>photolithograph\$)  | US-PGPUB;<br>USPAT; USOCR;<br>FPRS; EPO;<br>JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2009/12/26<br>18:11 |
| S38 | 0 | (hydrocarbon adj gas)<br>with (oxidation or<br>oxidizing or oxidized or<br>oxidize) with ((room or<br>ambient) near5<br>temperature or "25"<br>adj3 (celcius or<br>centigrade or degree))<br>and (lithograph\$ or<br>photolithograph\$)  | US-PGPUB;<br>USPAT; USOCR;<br>FPRS; EPO;<br>JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2009/12/26<br>18:11 |
| S39 | 1 | (hydrocarbon adj gas<br>or carbon near4<br>(residue or deposit or<br>contaminant or<br>contamination or<br>particle or particulate))<br>with (oxidation or<br>oxidizing or oxidized or<br>oxidize) with ((room or<br>ambient) near5<br>temperature or "25"<br>adj3 (celcius or<br>centigrade or degree))<br>and (lithograph\$ or<br>photolithograph\$) | US-PGPUB;<br>USPAT; USOCR;<br>FPRS; EPO;<br>JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2009/12/26<br>18:12 |

|     |   |   |   |    |    |                     |
|-----|---|---|---|----|----|---------------------|
| S40 | 0 | (hydrocarbon adj gas or carbon near4 (residue or deposit or contaminant or contamination or particle or particulate) near10 (oxidation or oxidizing or oxidized or oxidize) with ((room or ambient) near5 temperature or "25" adj3 (celcius or centigrade or degree)) and (lithograph\$ or photolithograph\$) | US-PGPUB;<br>USPAT; USOCR;<br>FPRS; EPO;<br>JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2009/12/26<br>18:12 |
| S41 | 1 | (hydrocarbon adj gas or carbon near4 (residue or deposit or contaminant or contamination or particle or particulate) with (oxidation or oxidizing or oxidized or oxidize) with ((room or ambient) near5 temperature or "25" adj3 (celcius or centigrade or degree)) and (lithograph\$ or photolithograph\$)   | US-PGPUB;<br>USPAT; USOCR;<br>FPRS; EPO;<br>JPO;<br>DERWENT;<br>IBM_TDB | OR | ON | 2009/12/26<br>18:12 |

### EAST Search History (I nterference)

< This search history is empty >

12/ 27/ 2009 3:46:22 PM

C:\ Documents and Settings\ scarrillo\ My Documents\ EAST\ Workspaces\ 10523371.wsp